## Highly-sensitive tunnel magnetoresistance sensor devices with NiFe/CoFeBTa free layers

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Tunnel magnetoresistance (TMR) sensors consisting of CoFeB/MgO/CoFeB magnetic tunnel junction (MTJ) has attracted much interest in the detection of small magnetic fields. The figure of merit of magnetic sensor is the magnetic field detectivity (*D*), defined by  $D = \frac{\sqrt{S_V}}{\Delta V/\Delta H}$ , where  $\sqrt{S_V}$  is noise voltage density in V/ $\sqrt{\text{Hz}}$ ,  $\Delta V$  is the full output voltage and  $\Delta H$  is the operating magnetic field range of the sensor [1]. We recently showed TMR sensors with linear and closed resistance (*R*)-field (*H*) curve using a top-pinned spin-valve TMR sensor with CoFeBTa (CFBT) (20)/Ta(0.3)/CoFe(3) free-layer (FL), where the CFBT layer is an amorphous soft-magnet [2]. The sensor's detectivity was as low as 2.2 nT/Hz<sup>0.5</sup> at 10 Hz. However, the sensor showed a wide  $\Delta H$  range of 2.5 mT. This means that there is a room to improve *D* by decreasing  $\Delta H$ .

In this talk, we present a technique to reduce  $\Delta H$  and thereby improve *D* by laminating NiFe with the CFBT/Ta/CFB FL. The TMR structures with different FLs are shown in Fig. 1(1 & 2). We applied a two-step annealing technique to obtain linear *R*-*H* curves. The first annealing step was performed at  $T_{1st}$ = 350 °C for 1 h under a horizontal magnetic field of 0.7 T. Thereafter, the samples were rotated by 90° and the second annealing step was performed at  $T_{2nd}$  = 200-220 °C for 20 min as shown in Fig. 1(3). Due to this annealing process, the pinning direction of spin-valve and the annealing-induced anisotropy in the FL are set orthogonally, which gives rise to linear *R*-*H* curves with small hysteresis as shown in Fig. 2.  $\Delta H$  was strongly decreased by introducing a thin layer of NiFe ( $t_{NiFe} \le 5$  nm) and then increased gradually for  $t_{NiFe} > 5$  nm (inset of Fig. 2). TMR ratio increased and reached to a maximum value for the MTJ sensor with NiFe 10/ CFBT 20/ Ta 0.3/CFBT 20 FL then decreased. The maximum magnetic field sensitivity S (= TMR/\DeltaH) has achieved for the MTJ sensor with NiFe 5/ CFBT 20/ Ta 0.3/CFBT 20 FL showed the noise voltage density  $\sqrt{S_V}$  of all MTJ sensors measured at the intermediate state of magnetization (1 mT) under a bias voltage of 30 mV. We have found that  $\sqrt{S_V}$  for all sensors. Remarkably, the MTJ sensor with NiFe 5/ CFBT 20/ Ta 0.3/CFBT 20 FL showed the minimum *D* of ~1.55 nT/Hz<sup>0.5</sup> at 10 Hz, which is lower than we previously reported [2].

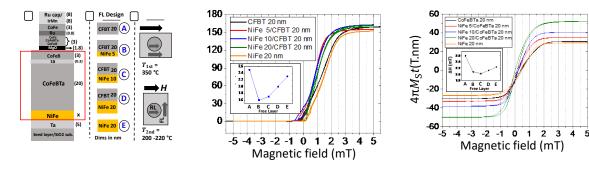
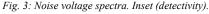


Fig. 1: (1) Layer structure, (2) FL designs (3) annealing technique.

Fig. 2: TMR-H curves. Inset ( $\Delta H$ ).



## References

[1] Silva et al. Eur. Phys. J. Appl. Phys. 72, 10601 (2015).

[2] Rasly et al. J. Phys. D: Appl. Phys. 54, 095002 (2021)